

Atty. Docket No. 2001-0108-1
USSN: 10/036,925

IN THE CLAIMS

Please amend claim 1 as follows:

1. (currently amended) A process for providing lithographic exposures utilizing a line narrowed gas discharge laser, comprising the steps of:
 - A. modeling with a computer program lithographic parameters to determine a desired laser spectrum needed to produce a desired lithographic result,
 - B. utilizing a fast responding tuning mechanism to adjust the center wavelength of substantially all laser pulses in a burst of pulses on a pulse-to-pulse basis to achieve an integrated spectrum for the burst of pulses approximating the desired laser spectrum.